

Recipe for photoresist AZ 5214E

Application

Substrate preparation: It is preferable to process the silicon substrate by evaporation of HMDS at 150°C for 45 seconds, using the Delta RC80.

Process

Tone	Negative
Special	Image Reversal
Reference	Merck
Spin coat	1.5 μm @4000 RPM
Pre bake	1 min @ 105°C (+10°C 5" wafer) on hotplate
Exposure time	1 sec @ 17,4 mW/cm ²
Post exposure bake (PEB)	1 min @ 120°C in oven
2 nd flood exposure time	15 sec
Development	90 sec in MF321
Stopping of development	30 sec in H ₂ O

Results

Spin curve

